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GRW/MT
Attorney for Applicants

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Appl. No.	:	10/849,348	Confirmation No.: 6690
Applicant	:	Robert H. Burgener, II et al.	
Title	:	GROUP II-VI SEMICONDUCTOR DEVICES	
Filed	:	May 19, 2004	
TC/A.U.	:	2814	
Examiner	:	Wai Sing Louie	
Docket No.	:	3398.2.10	
Customer No.	:	21552	

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

TRANSMITTAL OF SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Dear Sir:

Transmitted herewith is an Information Disclosure Statement disclosing information which has come to the attention of applicants and/or their attorneys and is being submitted so as to comply with the duty of disclosure set forth in 37 C.F.R. § 1.56. In accordance with 37 C.F.R. § 1.97(c), the enclosed Statement is being filed before the mailing date of either a final action or a notice of allowance and is accompanied by credit card payment form in the amount of One Hundred Eighty Dollars (\$180.00) to cover the fee set forth in 37 C.F.R. § 1.17(p).

Neither applicants nor their attorneys make any representation that any information disclosed herein may be "prior art" within the meaning of that term under 35 U.S.C. § 102 or § 103. Moreover, pursuant to 37 C.F.R. § 1.97, the filing of this Information Disclosure Statement

shall not be construed as a representation that a search has been made or as an admission that the information cited herein is, or is considered to be, material to patentability as defined in 37 C.F.R. § 1.56(b).

In accordance with 37 C.F.R. § 1.98, transmitted herewith are:

1. A completed copy of Forms PTO/SB/08a and PTO/SB08b "Information Disclosure Statement by Applicant" listing the patents, publications and other information being submitted for consideration; and
2. A legible copy of each patent, publication and other item of information in written form listed on the enclosed Forms PTO/SB/08a and PTO/SB/08b, except for copies of U.S. patents and published U.S. patent applications which are not required for applications filed after June 30, 2003.

Respectfully submitted,



Evan R. Witt
Reg. No. 32,512
Attorney for Applicants

Date: October 3, 2005

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PTO/SB/08a (08-03)

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Substitute for form 1449A/PTO		Complete if Known	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Application Number	10/849,348
(use as many sheets as necessary)		Filing Date	May 19, 2004
Sheet 1 Of 1		First Named Inventor	Robert H. Burgener, II
		Group Art Unit	2814
		Examiner Name	Wai Sing Louie
		Attorney Docket Number	3398.2.10

U.S. PATENT DOCUMENTS					
Examiner Initials *	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number - Kind Code ² (if known)			
U1	US-2004/0061114 A1		04/01/2004	Yan et al.	
U2					
U3					
U4					
U5					
U6					
U7					
U8					
U9					
U10					
U11					
U12					
U13					
U14					

FOREIGN PATENT DOCUMENTS					
Examiner Initials*	Cite No. ¹	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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Sheet 1 Of 9

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First Named Inventor	Robert H. Burgener, II
Group Art Unit	2814
Examiner Name	Wai Sing Louie
Attorney Docket Number	3398.2.10

NON PATENT LITERATURE DOCUMENTS

Examiner Initials *	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
O1		AULBUR, W.; Density Functional Theory: Basic Ideas & Applications; Ohio State University.	•
O2		LOOK, D.C., and CLAFLIN, B.; P-type doping and devices based on ZnO; 08/2003; Wiley-VCH Verlag GmbH & Co.	•
O3		ZUNGER, A.; Practical Doping Principles; NCPV and Solar Program Review Meeting 2003; pp. 831-835.	•
O4		ZHANG, S.B., WEI, S.H., and ZUNGER, A.; Intrinsic <i>n</i> -type versus <i>p</i> -type doping asymmetry and the defect physics of ZnO; Physical Review B; 01/31/2001; pp. 075205-1 - 075205-7; Volume 63; The American Physical Society.	•
O5		LIMPIJUMNONG, S., ZHANG, S.B., WEI, S-H., and PARK C.H.; Doping by Large-Size-Mismatched Impurities: The Microscopic Origin of Arsenic- or Antimony-Doped <i>p</i> -Type Zinc Oxide; Physical Review Letters; 04/16/2004; Volume 92, Number 15; The American Physical Society.	•
O6		YAMAMOTO, T., and KATAYAMA-YOSHIDA, H.; Solution Using a Codoping Method to <i>Unipolarity</i> for the Fabrication of <i>p</i> -Type ZnO; Japanese Journal of Applied Physics; 02/15/1999; pp. L 166-L 169; Volume 38; Japanese Journal of Applied Physics Publication Board.	•
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O11		NORTON, D.P., HEO, Y.W., IVILL, M.P., IP, K., PEARTON, S.J., et al; ZnO: growth, doping and processing; Materialstoday; 06/2004; Elsevier Ltd.	•
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Examiner Signature	Date Considered
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Substitute for form 1449B/PTO		Complete if Known	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(use as many sheets as necessary)</i>		Application Number	10/849,348
		Filing Date	May 19, 2004
		First Named Inventor	Robert H. Burgener, II
		Group Art Unit	2814
		Examiner Name	Wai Sing Louie
		Attorney Docket Number	3398.2.10
Sheet 2 Of 9			

	O15	WILKINSON, J., XIONG, G., UCER, K.B., and WILLIAMS, R.T.; Lifetime and Oscillator Strength of Excitonic Luminescence in Zinc Oxide; Department of Physics, Wake Forest University, Winston-Salem, NC.	
	O16	KOBAYASHI, A., SANKEY, O.F., and DOW, J.D.; Deep energy levels of defects in the wurtzite semiconductors AlN, CdS, CdSe, and ZnO; Physical Review B; 07/15/1983; pp. 946-956; Volume 28, Number 2; The American Physical Society.	
	O17	DANEU, N., REENIK, A., and BERNIK, S.; Grain Growth Control in Sb ₂ O ₃ -Doped Zinc Oxide; Journal of the American Ceramic Society; 2003; pp. 1379-1384; Volume 86, Number 8.	
	O18	OHYAMA, M.; Sol-Gel Preparation of Transparent and Conductive Aluminum-Doped Zinc Oxide Films with Highly Preferential Crystal Orientation; Journal of the American Ceramic Society; 1998; pp. 1622-1632; Volume 81, Number 6.	
	O19	DUAN, X.L., YUAN, D.R., CHENG, X.F., SUN, H.Q., SUN, Z.H., et al; Microstructure and Properties of Co ²⁺ ZnAl ₂ O ₄ /SiO ₂ Nanocomposite Glasses Prepared by Sol-Gel Method; Journal of the American Ceramic Society; 2005; pp. 399-403; Volume 88, Number 2.	
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	O24	QIU, C., CHEN, H., WONG, M., and KWOK, H.S.; Dependence of the Current and Power Efficiencies of Organic Light-Emitting Diode on the Thickness of the Constituent Organic Layers; IEEE Transactions On Electron Devices; 09/2001; pp. 2131-2137; Vol. 48; IEEE.	
	O25	MATSUDA, T., KAWABE, M., IWATA, H., and OHZONE, T.; Visible Electroluminescence from MOS Capacitors with Si-Implanted SiO ₂ ; IEICE Trans. Electron.; 09/11/2002; pp. 1895-1904; Vol. E85-C, No. 11.	
	O26	ONG, H.C., LI, A.S.K., and DU, G.T.; Depth profiling of ZnO thin films by cathodoluminescence; Applied Physics Letters; 04/30/2001; pp. 2667-2669; Vol. 78, No. 18; American Institute of Physics.	
	O27	WASHINGTON, P.L., ONG, H.C., DAI, J.Y., and CHANG, R.P.H.; Determination of the optical constants of zinc oxide thin films by spectroscopic ellipsometry; Applied Physics Letter; 06/22/1998; pp. 3261-3263; Vol. 72, No. 25; American Institute of Physics.	
	O28	SEKIGUCHI, T., OHASHI, N., and YAMANE, H.; Cathodoluminescence Study on ZnO and GaN; Solid State Phenomena; 1998; pp. 171-182; Vols. 63-64; Scitec Publications; Switzerland.	
	O29	KOUYATE, D., RONFARD-HARET, J.-C., and KOSSANYI, J.; Photo- and electroluminescence of rare earth-doped semiconducting zinc oxide electrodes: Emission from both the dopant and the support; Journal of Luminescence; 1991; pp. 205-210; Vol. 50; Elsevier Science Publishers B.V.	

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Sheet 3 Of 9

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Application Number 10/849,348

Filing Date May 19, 2004

First Named Inventor Robert H. Burgener, II

Group Art Unit 2814

Examiner Name Wai Sing Louie

Attorney Docket Number 3398.2.10

O30	KOSSANYI, J., KOUYATE, D., POULIQUEN, J., RONFARD-HARET, J.C., VALAT, P., et al.; Photoluminescence of Semiconducting Zinc Oxide Containing Rare Earth Ions as Impurities; Journal of Luminescence; 1990; pp. 17-24; Vol. 46; Elsevier Science Publishers B.V. (north-Holland).	3
O31	WANG, Y.G., LAU, S.P., LEE, H.W., YU, S.F., TAY, B.K., et al.; Photoluminescence study of ZnO films prepared by thermal oxidation of Zn metallic films in air; Journal of Applied Physics; 07/01/2003; pp. 354-358; Vol 94, No.1; American Institute of Physics.	•
O32	YU, S.F., YUEN, C., LAU, S.P., WANG, Y.G., LEE, H.W., et al.; Ultraviolet amplified spontaneous emission from zinc oxide ridge waveguides on silicon substrate; Applied Physics Letter; 11/24/2003; pp. 4288-4290; Vol. 83, No. 21; American Institute of Physics.	•
O33	XIONG, G., WILKINSON, J., LYLES, J., UCER, K.B., and WILLIAMS, R.T.; Luminescence and stimulated emission in zinc oxide nanoparticles, films, and crystals.	6
O34	ONG, H.C., DAI, J.Y., and DU, G.T.; Studies of electronic structure of ZnO grain boundary and its proximity by using spatially resolved electron energy loss spectroscopy; Applied Physics Letter; 07/08/2002; pp. 277-279; Vol. 81, No. 2; American Institute of Physics.	•
O35	AGNE, T., GUAN, Z., LI, X.M., WOLF, H., and WICHERT, T.; Incorporation of the Donor Indium in Nanocrystalline ZnO; phys. stat. sol.; 2002; pp. 819-823; Vol. 229; WILEY-VCH Verlag Berlin GmbH; Berlin.	•
O36	QADRI, S.B., KIM, H., HORWITZ, J.S., and CHRISEY, D.B.; Transparent conducting films of ZnO-ZrO ₂ : Structure and properties; Journal of Applied Physics; 12/01/2000; pp. 6564-6566; Vol. 88, No. 11; American Institute of Physics.	•
O37	HAN, J., MANTAS, P.Q., and SENOS, A.M.R.; Grain growth in Mn-doped ZnO; Journal of the European Ceramic Society; 2000; 2753-2758; Vol. 20.	•
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O40	COUNIO, G., ESNOUF, S., GACOIN, T., and BOILLOT, J.-P.; CdS:Mn Nanocrystals in Transparent Xerogel Matrices: Synthesis and Luminescence Properties; J. Phys. Chem.; 1996; pp. 20021-20026; Vol. 100; American Chemical Society.	•
O41	STRAVREV, K., KYNEV, K., ST. NIKOLOV, G., and DYAKOVITCH, V.A.; Semiempirical Assignment of the Electron Transitions in Manganese(II)-Doped II-VI Compounds; J. Phys. Chem. Solids; 1987; pp. 841-844; Vol. 48, No. 9; Pergamon Journals Ltd.	•
O42	FALCONY, C., ORTIZ, A., DOMINGUEZ, J.M., FARIAS, M.H., COTA-ARAIZA, L. et al.; Luminescent Characteristics of Tb Doped Al ₂ O ₃ Films Deposited by Spray Pyrolysis; J. Electrochem Soc.; 01/1992; pp. 267-271; Vol. 139, No. 1; The Electrochemical Society, Inc.	•
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		Examiner Name	Wai Sing Louie
		Attorney Docket Number	3398.2.10

O46	ARKLES, B.; Commercial Applications of Sol-Gel-Derived Hybrid Materials; MRS Bulletin; 05/2001; pp. 402-407.	•
O47	MURRAY, C.E., NOYAN, I.C., and MOONEY, P.M.; Mapping of strain fields about thin film structures using x-ray microdiffraction; Applied Physics Letters; 11/17/2003; pp. 4163-4165; Vol. 83, No. 20; American Institute of Physics.	•
O48	MODENA, S., SORARU, G.D., BLUM, Y., and RAJ, R.; Passive Oxidation of an Effluent System: The Case of Polymer-Derived SiCO; Journal of the American Ceramic Society; 2005; pp. 339-345; Vol. 88.	•
O49	NOYAN, I.C., WANG, P.-C., KALDOR, S.K., and JORDAN-SWEET, J.L.; Deformation field in single-crystal fields semiconductor substrates caused by metallization features; Applied Physics Letters; 04/19/1999; pp. 2352-2354; Vol. 74, No. 16; American Institute of Physics.	•
O50	NOYAN, I.C., JORDAN-SWEET, J., LINIGER, E.G., and KALDOR, S.K.; Characterization of substrate-thin-film interfaces with x-ray microdiffraction; Applied Physics Letters; 06/22/1998; pp. 3338-3340; Vol. 72, No. 25; American Institute of Physics.	•
O51	TULLER, H.L.; ZnO Grain Boundaries: Electrical Activity and Diffusion; Journal of Electroceramics; 1999; pp. 33-40; Vol. 4:S1; Kluwer Academic Publishers; Boston.	•
O52	WESTIN, G., EKSTRAND, A., NYGREN, M., OSTERLUND, R., and MERKELBACH, P.; Preparation of ZnO-based Varistors by the Sol-Gel Technique; J. Mater. Chem.; 1994; pp. 615-621; Vol. 4.	•
O53	WANG, M., YANG, X., and WANG, F.; Properties of Sensitive Materials Mainly Composed of ZnO; J. Mater. Sci. Technol.; 2000; p. 204; Vol. 16, No. 2.	•
O54	BAPTISTA, J.L., and MANTAS, P.Q.; High Temperature Characterization of Electrical Barriers in ZnO Varistors; Journal of Electroceramics; 2000; pp. 215-224; Vol. 4:1; Kluwer Academic Publishers; The Netherlands.	•
O55	BRANKOVIC, Z., BRANKOVIC, G., POLETI, D., and VARELA, J.A.; Structural and electrical properties of ZnO varistors containing different spinel phases; Ceramics International; 2001; pp. 115-122; Vol. 27; Elsevier Science Ltd. And Techna S.r.l.	•
O56	TANAKA, A., and MUKAE, K.; Evaluation of Single Grain Boundaries in ZnO: Rare-Earth Varistor by Micro-Electrodes; Key Engineering Materials; 1999; pp. 235-240; Vols. 157-158; Trans Tech Publications, Switzerland; CSJ Series-Publications of the Ceramic Society of Japan Vol. 1, The Ceramic Society of Japan.	•
O57	PANDEY, R., JAFFE, J.E., and KUNZ, A.B., <i>Ab initio</i> band-structure calculations for alkaline-earth oxides and sulfides; Physical Review B; 04/15/1991; pp. 9228-9237; Vol. 43, No. 11; The American Physical Society.	•
O58	CANNEY, S.A., SASHIN, V.A., FORD, M.J., and KHEIFETS, A.S.; Electronic band structure of magnesium and magnesium oxide: experiment and theory; J. Phys. Condens. Matter; 1999; pp. 7507-7522; Vol. 11; IOP Publishing Ltd.	•
O59	YAMASAKI, A., and FUJIWARA, T.; Electronic structure of the MO oxides (M=Mg, Ca, Ti, V) in the GW approximation; Physical Review B; 2002; pp. 245108-1 – 245108-9; Vol. 66; The American Physical Society.	•
O60	MIKALO, E.A., SASHIN, V.A., NIXON, K.L., SEOULE DE BAS, B., DORSETT, H.E., and FORD, M.J.; Band Structures of the Group I and II Oxides: Using EMS Measurements as a Test of Theoretical Models.	•
O61	JOHNSON, P.D.; Some Optical Properties of MgO in the Vacuum Ultraviolet; Physical Review; 05/15/1954; pp. 845-846; Vol. 94, No. 4.	•

Examiner Signature		Date Considered	
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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Sheet 5 Of 9

Complete if Known

Application Number	10/849,348
Filing Date	May 19, 2004
First Named Inventor	Robert H. Burgener, II
Group Art Unit	2814
Examiner Name	Wai Sing Louie
Attorney Docket Number	3398.2.10

O62	NARAZAKI, A., TANAKA, K., HIRAO, K., HASHIMOTO, T., NASU, H., et al.; IR and XPS Studies on the Surface Structure of Poled ZnO-TeO ₂ Glasses with Second-Order Nonlinearity; Journal of the American Ceramic Society; 2001; pp. 214-217; Vol. 84.	•
O63	SCHONBERGER, U., and ARYASSETIawan, F.; Bulk and surface electronic structures of MgO; Physical Review B; 09/15/1995; pp. 8788-8793; Vol. 52, No. 12; The American Physical Society.	•
O64	GONZALEZ, R., CHEN, Y., SEBEK, R.M., WILLIAMS, G.P., WILLIAMS, R.T., et al.; Properties of the 800-nm luminescence band in neutron-irradiated magnesium oxide crystals; Physical Review B; 03/01/1991; pp. 5228-5233; Vol. 43, No. 7; The American Physical Society.	•
O65	BALZER, B., HAGEMEISTER, M., KOCHER, P., and LUDWIG, J.G.; Mechanical Strength and Microstructure of Zinc Oxide Varistor Ceramics; Journal of the American Ceramic Society; 2004; pp. 1932-1938; Vol. 87.	•
O66	SHENG, H., EMANETOGLU, N.W., MUTHUKUMAR, S., YAKSHINSKIY, B.V., FENG, S., et al.; Ta/Au Ohmic Contacts to n_type ZnO; Journal of Electronic Materials; 2003; p. 935; Vol. 32, No. 9.	•
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O68	XIONG, G., WILKINSON, J., MISCHUCK, B., TU'ZEMEN, S., UCER, K.B., et al; Control of p- and n-type conductivity in sputter deposition of undoped ZnO; Applied Physics Letters; 02/18/2002; p. 1195; Vol. 80, No. 7.	•
O69	YAMAMOTO, T., and KATAYAMA-YOSHIDA, H.; Unipolarity of ZnO with a wide-band gap and its solution using codoping method; Journal of Crystal Growth; 2000; pp. 552-555; Vol. 214/215; Elsevier Science B.V.	•
O70	CHANG, R., MARKS, T., MASON, T., and POEPPELMEIR, K.; n/p-Type Transparent Conductors; pp. 259-260.	•
O71	OLORUNYOLEMI, T., BIRNBOIM, A., CARMEL, Y., WILSON, O.C., LLOYD, I.K.; Thermal Conductivity of Zinc Oxide: From Green to Sintered State; Journal of the American Ceramic Society; 2002; pp. 1249-1253; Vol. 85.	•
O72	MARTIN, L.P., and ROSEN, M.; Correlation between Surface Area Reduction and Ultrasonic Velocity in Sintered Zinc Oxide Powders; Journal of the American Ceramic Society; 1997; pp. 839-846; Vol. 80.	•
O73	WILKINSON, J., XIONG, G., UCER, K.B., and WILLIAMS, R.T.; Lifetime and Oscillator Strength of Excitonic Luminescence in Zinc Oxide.	•
O74	SEKIGUCHI, T., HAGA, K., and INABA, K.; ZnO films grown under the oxygen-rich condition; Journal of Crystal Growth; 2000; pp. 68-71; Vol. 214-215; Elsevier Science B.V.	•
O75	VAN DE WALLE, C.G.; Hydrogen as a Cause of Doping in Zinc Oxide; Physical Review Letters; 07/31/2000; pp. 1012-1015; Vol. 85, No. 5; The American Physical Society.	•
O76	KATO, H., SANO, M., MIYAMOTO, K., and YAO, T.; Effect of O/Zn on Flux Ratio on Crystalline Quality of ZnO Films Grown by Plasma-Assisted Molecular Beam Epitaxy; Japanese Journal of Applied Physics; 2003; pp. 2241-2244; Vol. 42; The Japan Society of Applied Physics.	•
O77	NAKAHARA, K., TANABE, T., TAKASU, H., FONS, P., IWATA, K., et al.; Growth of undoped ZnO Films with Improved Electrical Properties by Radical Source Molecular Beam Epitaxy; Japanese Journal of Applied Physics; 2001; pp. 250-254; Vol. 40; The Japan Society of Applied Physics.	•

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Sheet 6 Of 9

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Filing Date	May 19, 2004
First Named Inventor	Robert H. Burgener, II
Group Art Unit	2814
Examiner Name	Wai Sing Louie
Attorney Docket Number	3398.2.10

O78	WANG, X., DU, G., GU, C., JIA, J., LI, X., et al.; Two-step growth of ZnO thin films on diamond/Si low-pressure metal-organic chemical vapour deposition; <i>J. Phys. D: Appl. Phys.</i> ; 2002; pp. L74-L76; Vol. 35; IOP Publishing Ltd., United Kingdom.	✓
O79	HAN, J., MANTAS, P.Q., and SENOS, A.M.R.; Grain growth in Mn-doped ZnO; <i>Journal of the European Ceramic Society</i> ; 2000; pp. 2753-2758; Vol. 20; Elsevier Science Ltd.	✓
O80	FONS, P., IWATA, K., NIKI, S., YAMADA, A., MATSUBARA, K., et al.; Uniaxial locked growth of high-quality epitaxial ZnO films on (1 1 2 0) α -Al ₂ O ₃ ; <i>Journal of Crystal Growth</i> ; 2000; pp. 532-536; Vol. 209; Elsevier Science B.V.	✓
O81	HAGA, K., KAMIDAIRA, M., KASHIWABA, Y., SEKIGUCHI, T., WATANABE, H.; ZnO thin films prepared by remote plasma-enhanced CVD method; <i>Journal of Crystal Growth</i> ; 2000; pp. 77-80; Vol. 214/215; Elsevier Science B.V.	✓
O82	FONS, P., IWATA, K., NIKI, S., YAMADA, A., and MATSUBARA, K.; Growth of high-quality epitaxial ZnO films on α -Al ₂ O ₃ ; <i>Journal of Crystal Growth</i> ; 1999; pp. 627-632; Vol. 201/202; Elsevier Science B.V.	✓
O83	MYOUNG, J.-M., YOON, W.-H., LEE, D.-H., YUN, I., BAE, S.-H., et al.; Effects of Thickness Variation of Properties of ZnO Thin Films Grown by Pulsed Laser Deposition; <i>Japanese Journal of Applied Physics</i> ; 2002; pp. 28-31; Vol. 41; The Japan Society of Applied Physics.	✓
O84	YULDASHEV, S.U., PANIN, G.N., CHOI, S.W., YALISHEV, V.S., NOSOVA, L.A., et al.; Electrical and Optical Properties of ZnO Films Grown on GaAs Substrates; <i>Jpn. J. Appl. Phys.</i> ; 2003; pp. 3333-3336; Vol. 42; The Japan Society of Applied Physics.	✓
O85	NONAKA, M., MATSUSHIMA, S., MIZUNO, M., KOBAYASHI, K.; Electronic Structure of Group III Elements Doped into ZnO by Using Molecular Orbital Calculation; <i>Chemistry Letters</i> ; 2002; pp. 580-581; The Chemical Society of Japan.	✓
O86	LIN, G.-R., and WANG, S.-C.; Comparison of High-Resistivity ZnO Films Sputtered on Different Substrates; <i>Japanese Journal of Applied Physics</i> ; 2002; pp. L398-L401; Vol. 41; The Japan Society of Applied Physics.	✓
O87	MANTAS, P.Q., and BAPTISTA, J.L.; The Barrier Height Formation in ZnO Varistors; <i>Journal of the European Ceramic Society</i> ; 1995; pp. 605-615; Vol. 15; Elsevier Science Limited, Great Britain.	✓
O88	ALBERTSSON, J., and ABRAHAMS, S.C.; Atomic Displacement, Anharmonic Thermal Vibration, Expansivity and Pyroelectric Coefficient Thermal Dependences in ZnO; <i>Acta Cryst.</i> ; 1989; pp. 34-40; Vol. B45; International Union of Crystallography.	✓
O89	BLEVINS, J.D.; Wide Bandgap Semiconductor Substrates: Current Status and Future Trends.	✓
O90	TEKE, A., OZGUR, U., DOGAN, S., GU, X., MORKOC, H., et al.; Excitonic fine structure and recombination dynamics in single-crystalline ZnO; <i>Physical Review B</i> ; 2004; pp. 195207-1 – 195207-10; Vol. 70; The American Physical Society.	✓
O91	LOOK, D.C., REYNOLDS, D.C., LITTON, C.W., JONES, R.L., EASON, D.B., et al.; Characterization of homoepitaxial <i>p</i> -type ZnO grown by molecular beam epitaxy; <i>Applied Physics Letters</i> ; 09/02/2002; pp. 1830-1832; Vol. 81, No. 10; American Institute of Physics.	✓
O92	KIM, K.-K., KIM, H.-S., HWANG, D.-K., LIM, J.-H., and PARK, S.-J.; Realization of <i>p</i> -type ZnO thin films via phosphorus doping and thermal activation of the dopant; <i>Applied Physics Letters</i> ; 07/07/2003; pp. 63-65; Vol. 83, No. 1; American Institute of Physics.	✓
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(use as many sheets as necessary)		Filing Date	May 19, 2004
Sheet 7 Of 9		First Named Inventor	Robert H. Burgener, II
		Group Art Unit	2814
		Examiner Name	Wai Sing Louie
		Attorney Docket Number	3398.2.10

O94	SENGER, R.T., and BAJAI, K.K.; Binding energies of excitons in polar quantum well heterostructures; Physical Review B; 2003; pp. 205314-1 -205314-9; Vol. 68; The American Physical Society.	•
O95	SUBRAMANYAM, T.K., NAIDU, B., and UTHANNA, S.; Structure and Optical Properties of dc Reactive Magnetron Sputtered Zinc Oxide Films; Cryst. Res. Technol.; 1999; pp. 981-988; Vol. 34.	•
O96	MUTH, J.F., BROWN, J.D., JOHNSON, M.A.L., YU, Z., KOLBAS, R.M., et al.; Absorption coefficient and refractive index of GaN, AlN and AlGaN alloys; 1999; MRS Internet J. Nitride Semicond.	•
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O99	NEETHLING, J.H., SCRIVEN, G.J., and KREKELS, T.; A TEM investigation of Zn ₃ As ₂ grown on (001) and (111) InP by MOVPE; Journal of Materials Science; 2001; pp. 3997-4002; Vol. 36; Kluwer Academic Publishers.	•
O100	BRINK, D.J., and ENGELBRECHT, A.A.; Ellipsometric investigation of rough zinc arsenide epilayers; Applied Optics; 04/01/2002; pp. 1894-1898; Vol. 41, No. 10; Optical Society of America.	•
O101	SCRIVEN, G.J., LEITCH, A.W.R., NEETHLING, J.H., KOZYRKOV, V.V., and WATTERS, V.J.; The growth of Zn ₃ As ₂ on InP by atmospheric pressure MOVPE; Journal of Crystal Growth; 1997; pp. 813-816; Vol. 170; Elsevier Science B.V.	•
O102	ENGELBRECHT, J.A.A., SCRIVEN, G.J., NEETHLING, J.H., and WAGENER, M.C.; Crack formation in Zn ₃ As ₂ epilayers grown by MOVPE; Journal of Crystal Growth; 2000; pp. 235-244; Vol. 216; Elsevier Science B.V.	•
O103	NORMAN, A.G., OLSON, J.M., ROMERO, M.J., and AL-JASSIM, M.M.; Electron Microscopy Studies of Potential 1-eV Bandgap Semiconductor Compounds AnGeAs ₂ and Zn ₃ As ₂ Grown by MOVPE; National Renewable Energy Laboratory.	•
O104	MILES, G.C., and WEST, A.R.; Polymorphism and Thermodynamic Stability of Zn ₇ Ab ₂ O ₁₂ ; Journal of the American Ceramic Society; 2005; pp. 396-398; Vol. 88.	•
O105	TOMLINS, G.W., ROUTBORT, J.L., and MASON, T.O.; Oxygen Diffusion in Single-Crystal Zinc Oxide; Journal of the American Ceramic Society; 1998; pp. 869-876; Vol. 81.	•
O106	BOTHA, J.R., SCRIVEN, G.J., ENGELBRECHT, J.A.A., and LEITCH, A.W.R.; Photoluminescence properties of metalorganic vapor phase epitaxial Zn ₃ As ₂ ; Journal of Applied Physics; 11/15/1999; pp. 5614-5618; Vol. 86, No. 10; American Institute of Physics.	•
O107	XIONG, G., WILKINSON, J., MISCHUCK, B., TUZEMEN, S., UCER, K.B., et al.; Control of <i>p</i> - and <i>n</i> -type conductivity in sputter deposition of undoped ZnO; Applied Physics Letters; 02/18/2002; pp. 1195-1197; Vol. 80, No. 7; American Institute of Physics.	•
O108	LOOK, D.C., RENLUND, G.M., BURGENER, II, R.H., and SIZELOVE, J.R.; As-doped <i>p</i> -type ZnO produced by an evaporation/sputtering process; Applied Physics Letters; 11/2004; Vol. 85.	•
O109	AOKI, T., SHIMIZU, Y., MIYAKE, A., NAKAMURA, A., NAKANISHI, Y., and HATANAKA, Y.; <i>p</i> -Type ZnO Layer Formation by Excimer Laser Doping; phys. stat. sol.; 2002; pp. 911-914; Vol. 229, No. 2; WILEY-VCh Verlag Berlin GmbH, Berlin.	•

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Sheet 8 Of 9		First Named Inventor	Robert H. Burgener, II
		Group Art Unit	2814
		Examiner Name	Wai Sing Louie
		Attorney Docket Number	3398.2.10

O110	LEE, J-M., KIM, K.K., PARK, S-J., and CHOI, W.K.; Low-resistance and non-alloyed ohmic contacts to plasma treated ZnO; Applied Physics Letters; 06/11/2001; pp. 3842-2844; Vol. 78, No. 24; American Institute of Physics.	•
O111	YAMAMOTO, T.; Codoping Method to Realize Low-Resistivity p-type ZnO Thin Films; Asia Display/IDW '01, Oct. 16-19, 2001, Nagoya, Oct. 18, PH1-2.	•
O112	WANG, L.G., and ZUNGER, A.; Cluster-Doping Approach for Wide-Gap Semiconductors: The Case of p-type ZnO; Physical Review Letters; 06/27/2003; pp. 256401-1 - 256401-4; Vol. 90, No. 25; The American Physical Society.	•
O113	NAKAHARA, K., TAKASU, H., FONS, P., YAMADA, A., IWATA, K., et al.; Growth of N-doped and Ga+N-codoped ZnO films by radical source molecular beam epitaxy; Journal of Crystal Growth; 2002; pp. 503-508; Vol. 237-239; Elsevier Science B.V.	•
O114	RECNIK, A., DANEU, N., WALTHER, T., and MADER, W.; Structure and Chemistry of Basal-Plane Inversion Boundaries in Antimony Oxide-Doped Zinc Oxide; Journal of the American Ceramic Society; 2001; pp. 2357-2668; Vol. 84.	•
O115	NONAKA, M., MATSUSHIMA, S., MIZUNO, M., and KOBAYASHI, K.; Electronic Structure of Group III Elements Doped into ZnO by Using Molecular Orbital Calculation; Chemistry Letters; 2002; pp. 580-581; The Chemical Society of Japan.	•
O116	RYU, Y.R., KIM, W.J., and WHITE, H.W.; Fabrication of homostructural ZnO p-n junctions; Journal of Crystal Growth; 2000; pp. 419-422; Vol. 219; Elsevier Science B.V.	•
O117	LU, J., YE, Z., WANG, L., HUANG, J., and ZHAO, B.; Structural, electrical and optical properties of N-doped ZnO films synthesized by SS-CVD; Materials Science in Semiconductor Processing; 2003; pp. 491-496; Vol. 5; Elsevier Science Ltd.	•
O118	ZHENGUO, J., KUN, L., CHENGXING, Y., RUIXIN, F., and ZHIZHEN, Y.; Structural, optical and electrical properties of ZnO thin films prepared by reactive deposition; Journal of Crystal Growth; 2003; pp. 246-251; Vol. 253; Elsevier Science B.V.	•
O119	JI, Z., YANG, C., LIU, K., and YE, Z.; Fabrication and characterization of p-type ZnO films by pyrolysis of zinc-acetate—ammonia solution; Journal of Crystal Growth; 2003; pp. 239-242; Vol. 253; Elsevier Science B.V.	•
O120	YE, Z-Z., LU, J-G., CHEN, H-H., ZHANG, Y-Z., WANG, L., et al.; Preparation and characteristics of p-type ZnO films by DC reactive magnetron sputtering; Journal of Crystal Growth; 2003; pp. 258-264; Vol. 253; Elsevier Science B.V.	•
O121	MINEGISHI, K., KOIWAI, Y., KIKUCHI, Y., YANO, K., KASUGA, M., et al.; Growth of p-type Zinc Oxide Films by Chemical Vapor Deposition; Japanese Journal of Applied Physics; 1997; pp. L 1453 – L 1455; Vol. 36.	•
O122	JOSEPH, M., TABATA, H., and KAWAI, T.; p-Type Electrical Conduction in ZnO Thin Films by Ga and N Codoping; Japanese Journal of Applied Physics; 1999; pp. L 1205 – L 1207; Vol. 38; Publication Board, Japanese Journal of Applied Physics.	•
O123	ASHRAFI, A.B.M.A., SUEMUNE, I., KUMANO, H., and TANAKA, S.; Nitrogen-Doped p-Type ZnO Layers Prepared with H ₂ O Vapor-Assisted Metalorganic Molecular-Beam Epitaxy; Japanese Journal of Applied Physics; 2002; pp. L 1281 – L 1284; Vol. 41; The Japan Society of Applied Physics.	•
O124	The Promise of Solid State Lighting for General Illumination: Light Emitting Diodes (LEDs) and Organic Light Emitting Diodes (OLEDs); 2001; pp. 1-29; Optoelectronics Industry Development Association, Washington, D.C.	•
O125	TALBOT, D.; LEDs vs. the Light Bulb; Technology Review; 05/2003; pp. 30-36.	1

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Group Art Unit	2814
Examiner Name	Wai Sing Louie
Attorney Docket Number	3398.2.10

O126	JOHNSON, S.; LEDs—An Overview of the State of the Art in Technology and Application; Light Right 5 Conference, May 27-31, 2002, Nice, France.	✓
O127	TUZEMEN, S., XIONG, G., WILKINSON, J., MISCHICK, B., UCER, K.B., et al.; Production and properties of p-n junctions in reactively sputtered ZnO; Physica B; 2001; pp. 1197-1200; Vol. 308-310; Elsevier Science B.V.	✓
O128	GUO, X-L., CHOI, J-H., TABATA, H., and KAWAI, T.; Fabrication and Optoelectronic Properties of a Transparent ZnO Homostructural Light-Emitting Diode; Japanese Journal of Applied Physics; 2001; pp. L 177 – L 180; Vol. 40; The Japan Society of Applied Physics.	✓
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O130	HOFFMAN, R.L., NORRIS, B.J., and WAGER, J.F.; ZnO-based transparent thin-film transistors; Applied Physics Letters; 02/03/2003; pp. 733-735; Vol. 82, No. 5; American Institute of Physics.	✓
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